

Form PTO-1449 U.S. Department of Commerce (REV. 2-82) Patent and Trademark Office		Atty. Docket No. A34605 PCT-USA 072944.0168	Serial No. 09/914,440
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use several sheets if necessary)</i>		Applicant LEE et al.	
		Filing Date August 27, 2001	Group 1773
		Examiner Nikolas J. Uhlir	

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U.S. PATENT DOCUMENTS

*Exam. Init.	No.	Document No.							Date	Name	Class	Subclass	Filing Date if Appro.
<i>NY</i>		5	7	5	3	7	4	0	5/19/98	Odawa et al.			06/4/96

FOREIGN PATENT DOCUMENTS

	No.	Document No.	Date	Country	Class	Subclass	Translation Yes No
<i>NY</i>		3-074481	03/29/91	Japan			*
<i>NY</i>		5-255587	10/5/93	Japan			*
<i>NY</i>		8-53646	2/27/96	Japan			*
<i>NY</i>		44 41 883	5/30/96	Germany			*

No.	OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)
<i>NY</i>	Eastech Chemical, Inc., "PAPHEN(r) Phenoxy Resins", available at http://www.eastechchemical.com/prdc/func/docs/01-Phenoxy_Product_Guide.pdf (last accessed May 19, 2003).
<i>NY</i>	*English abstract is attached.

NY02:438451.1

Examiner



Date Considered



* Examiner: Initial citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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